

David L. Windt
Publications

Peer-Reviewed Journals

1. D. L. Windt and J. A. Bellotti, 'Performance, structure and stability of SiC/Al multilayer films for extreme ultraviolet applications', *App. Op.*, 48, 4932 – 4941 (2009)
2. D. L. Windt, J. A. Bellotti, B. Kjornrattanawanich, and J. F. Seely, 'Performance optimization of Si/Gd extreme ultraviolet multilayers', *App. Op.*, 48, 5502 -- 5508 (2009)
3. M. Suman, M. G. Pelizzo, D. L. Windt and P. Nicolosi, 'Extreme-ultraviolet multilayer coatings with high spectral purity for solar imaging', *App. Op.*, 48, 5432 – 5437 (2009)
4. B. Kjornrattanawanich, D. L. Windt, J. A. Bellotti and J. F. Seely, 'Measurement of dysprosium optical constants in the 2-830 eV spectral range using a transmittance method, and compilation of the revised optical constants of lanthanum, terbium, neodymium, and gadolinium', *App. Opt.*, 48, 3084 – 3093 (2009)
5. M. G. Pelizzo, M., G. Monaco, P. Nicolosi, David L. Windt, 'High performance EUV multilayer structures insensitive to capping layer optical parameters', *Opt. Exp.*, 165, 15228-15237 (2008)
6. M. Suman, M.-G. Pelizzo, P. Nicolosi, D. L. Windt, 'Aperiodic multilayers with enhanced reflectivity for extreme ultraviolet lithography', *App. Op.*, 47, 2906-2914 (2008)
7. B. Kjornrattanawanich, D. L. Windt and J. F. Seely, 'Normal-incidence silicon–gadolinium multilayers for imaging at 63 nm wavelength', *Opt. Lett.*, 33, 465 (2008)
8. R. Soufli, S. L. Baker, D. L. Windt, E. M. Gullikson, J. C. Robinson, W. A. Podgorski, and L. Golub, 'Atomic force microscopy characterization of Zerodur mirror substrates for the extreme ultraviolet telescopes aboard NASA's Solar Dynamics Observatory', *App. Opt.*, 46, 3156 – 3163 (2007)
9. B. Kjornrattanawanich, D. L. Windt, J. F. Seely and Yu. A. Uspenskii, 'SiC/Tb and Si/Tb multilayer coatings for EUV solar imaging', *App. Opt.*, 45, 1765 – 1772 (2006)
10. D. L. Windt, J. F. Seely, B. Kjornrattanawanich, and Yu. A. Uspenskii, 'Tb-based EUV multilayers', *Opt. Lett.*, 30, 3186 – 3188 (2005)
11. D. L. Windt, S. Donguy, J. F. Seely, B. Kjornrattanawanich, 'Experimental comparison of extreme-ultraviolet multilayers for solar physics', *App. Opt.*, 43, 1835 – 1848 (2004)
12. J. F. Seely, C. M. Brown, D. L. Windt, S. Donguy, B. Kjornrattanawanich, 'Normal-Incidence Efficiencies of Multilayer-Coated Laminar Gratings for the Extreme-Ultraviolet Imaging Spectrometer on the Solar-B Mission', *App. Op.*, 43, 1463 – 1471 (2004)
13. J. Dalla Torre, G. H. Gilmer, D. L. Windt, R. Kalyanaraman, F. H. Bauman, P. L. O'Sullivan, J. Sapjeta, T. Diaz de la Rubia, and M. Djafari Rouhani, 'Microstructure of thin tantalum films sputtered onto inclined substrates: experiments and atomistic simulations', *J. App. Phys.*, 94, 263 – 271 (2003)
14. D. L. Windt, S. Donguy, C. J. Hailey, J. Koglin, V. Honkimaki, E. Ziegler, F. E. Christensen, C. M. H. Chen, F. A. Harrison, W. W. Craig, 'W/SiC X-ray multilayers optimized for use above 100 keV', *App. Opt.*, 42, 2415 – 2421 (2003)
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19. F. E. Christensen, W. W. Craig, M. Jimenez-Garate, C. J. Hailey, F. A. Harrison, P. H. Mao, D. L. Windt, E. Ziegler, V. Honkimaki, M. S. Del Rio, A. Souvorov, and A. Freund, 'Measured reflectance of graded multilayer mirrors designed for astronomical hard X-ray telescopes', *Nucl. Instr. Meth. A*, 451, 572-581 (2000)
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59. D. L. Windt and B. Bach, 'Ion beam deposited silicon carbide on glass optics and replica gratings', *Appl. Op.*, 23, 3047 (1984)

Other Publications

1. D. L. Windt and J. A. Bellotti, 'SiC/Al multilayers for normal incidence EUV applications', *Proc. SPIE*, 7437-35 (2009)
2. J. A. Bellotti and D. L. Windt, 'Depth-graded Co/C multilayers prepared by reactive sputtering', *Proc. SPIE*, 7437-36 (2009)
3. D. L. Windt, 'Reduction of stress and roughness by reactive sputtering in W/B₄C multilayer films', *Proc. SPIE* 6688 (2007)
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8. J. F. Seely, B. Kjornrattanawanich, D. L. Windt and Yu. A. Uspenskii, 'Terbium-based multilayers and filters for imaging the solar O V 63.0 nm and Mg X 61.0 nm emission', *Proc. SPIE*, 5901 (2005)
9. F. Eriksson and D. L. Windt, 'Growth, structure and performance of new X-ray multilayers', *Proc. SPIE*, 5900, (2005)
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14. J. Seely, L. Goray, D. Windt, B. Kjornrattanawanich, Y. Uspenskii, and A. Vinogradov, 'Extreme ultraviolet optical constants for the design and fabrication of multilayer-coated gratings', *Proc. SPIE*, 5538 (2004)
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17. D. L. Windt, S. Donguy, J. Seely, B. Kjornrattanawanich, E. M. Gullikson, C. C. Walton, L. Golub, E. DeLuca, 'EUV multilayers for solar physics', *Proc. SPIE*, 5168, 1 – 11 (2003)
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27. F. E. Christensen, W. W. Craig, C. J. Hailey, M. A. Jimenez-Garate, D. L. Windt, F. A. Harrison, P. H. Mao, E. Ziegler, V. Honkimaki, M. S. Del Rio, A. K. Freund, M. Ohler, 'Hard X-ray characterization of a HEFT single reflection prototype', *Proc. SPIE*, 4012, 626-638 (2000)

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